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Polishing Selectivity Control for Scratch Free Nanoceria Slurry

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Conferment MS degree in industrial chemistry (organic chemistry), Tokyo University of science, 2008

Joined Hitachi Chemical co. Ltd. (company name change to Showa Denko Materials from 2020) and belong to R&D department.

From 2009 to 2015, in charge of nano-ceria slurry development.

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